AMENDMENTS TO THE CLAIMS:

The following listing of claims replaces all prior listings, and all prior versions, of claims in the application.

LISTING OF CLAIMS:

1. (Currently amended) A nanoprint apparatus for forming a fine structure on a substrate, in which the substrate and a mold, having formed on a~~its~~ surface of the mold~~with~~ fine concavities and convexities, are heated and pressed to each other through the intermediary of a buffer member, characterized by a mechanism for successively replacing the buffer member with new one after heating and pressing, and

wherein said buffer member is interposed between said mold and a head having a press surface, adjacent a surface of the mold opposite to the surface of the mold having fine concavities and convexities, or is interposed between the substrate and a stage for carrying the substrate.

2. (Original) A nanoprint apparatus as set forth in claim 1, characterized in that the buffer member is larger than a pattern forming area of the mold, but smaller than an external shape of the substrate and the external shape of the mold.

3. (Withdrawn) A method of transferring a pattern with the use of a nanoprint apparatus and with the use of a substrate, a mold formed on its surface with fine concavities and convexities and a buffer member so as to form a fine structure on the substrate, characterized in that:

a plurality of buffer members held on a conveying film are used, with one of which the buffer member is successively replaced after heating and pressing.

4. (Withdrawn) A method of transferring a pattern as set forth in claim 3, wherein the buffer member is larger than a pattern forming area of the mold, but smaller than an external shape of the substrate and the external shape of the mold.

5. (Withdrawn) A method of transferring a pattern, as set forth in claim 3, characterized in that pattern transcription is carried out by optical curing after press molding a resin substrate or a resin film on the substrate.

6. (Withdrawn) A method of transferring a pattern as set forth in claim 3, characterized in that pattern transcription is carried out by heating a resin substrate or a resin film on a substrate so as to deform the same.

7. (Withdrawn) A method of transferring a pattern as set forth in claim 3, characterized in that pattern transcription is carried out by irradiating a light beam from above the mold so as to optically cure a resin substrate or a resin film on the substrate.

8. (Previously presented) A nanoprint apparatus as set forth in claim 1, wherein said buffer member is made of a material selected from the group consisting of polyimide, polytetrafluoroethylene and silicone rubber.

9. (Previously presented) A nanoprint apparatus as set forth in claim 1, wherein said buffer member is made of a material selected from the group consisting of polyethylene terephthalate, polyethylene and acrylonitrile butadiene rubber.

10. (Currently amended) A nanoprint apparatus as set forth in claim 1, ~~further comprising a head having a press surface, adjacent a surface of the mold opposite to the surface thereof having fine concavities and convexities, and~~ wherein said buffer member is interposed between the mold and the head.

11. (Currently amended) A nanoprint apparatus as set forth in claim 1, wherein said buffer member is positioned interposed between the substrate and said~~a~~ stage for carrying the substrate.